

Comparative studies of defect behaviour in deuterated and nondeuterated n-type Si

J. H. Bleka,¹ E. V. Monakhov,¹ A. Ulyashin,¹ A. Yu. Kuznetsov,¹ B. S. Avset² and B. G. Svensson¹

¹Department of Physics, Physical Electronics, University of Oslo

²SINTEF ICT, Microsystems

Outline



- Hydrogen related defects in high-purity, low-doped FZ Si
- Previous results from hydrogenated samples
- Comparision with deuterated samples
- Comparision of samples with different deuterium concentration

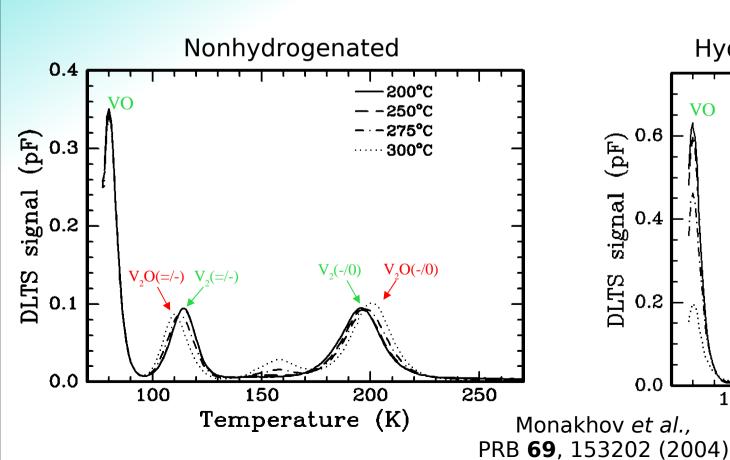
Background

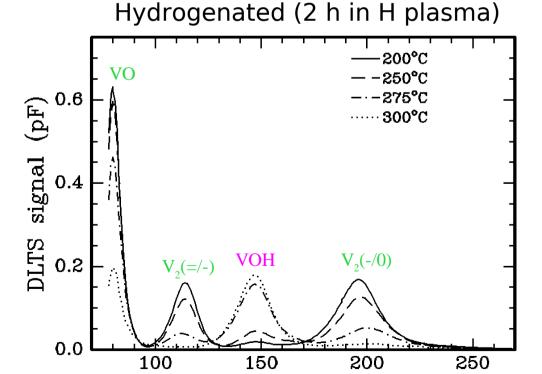


Previous claims of the process $V_2 + O \rightarrow V_2O$

...and hydrogen-assisted annealing of V_2

$$V_2 + H_2 \rightarrow V_2 H_2$$
?





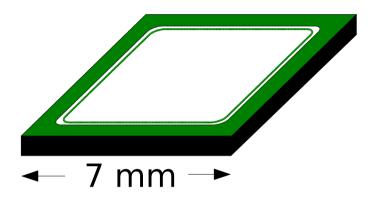
Temperature (K)

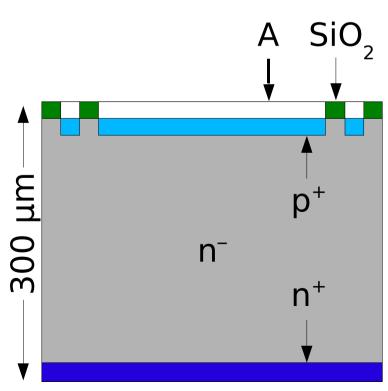
Experimental details



p⁺-n⁻-n⁺ Si diodes

- produced from high-purity FZ wafers (5×10¹² P/cm³)
- oxidation: 21 h dry at 1200 °C
- oxygenation: 80 h in N₂ at 1150 °C
- ordinary diode processing
- 2 and 4 hour deuteration:
 n⁺ side exposed to D plasma
 (T=150 °C, P=700 mTorr)
- 6-MeV electron **irradiation**: 1×10^{12} cm⁻³





Results and discussion



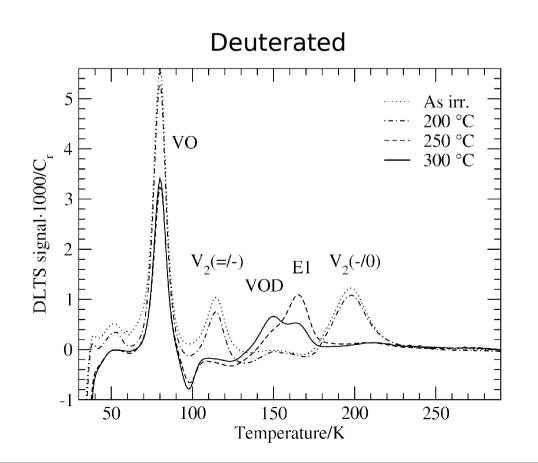
$$V_2 + O \rightarrow V_2O$$

VO peak stable

Nondeuterated As irr. 200 °C VO DLTS signal·1000/C_r 300 °C $V_{2}(=/-)$ $V_{2}(-1/0)$ $V_{2}O(-1/0)$ $V_2O(=/-)$ 50 100 150 200 250 Temperature/K



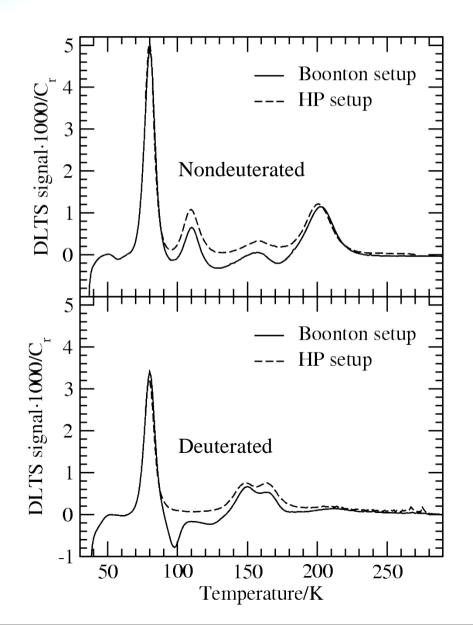
No peak below 77 K identified as V_2D_2 (V_2H_2) Could E1 be due to $V_2 + D_2 \rightarrow V_2D_2$?



Results and discussion

Boonton 7200 C meter vs.
HP 4280A C meter





Results and discussion

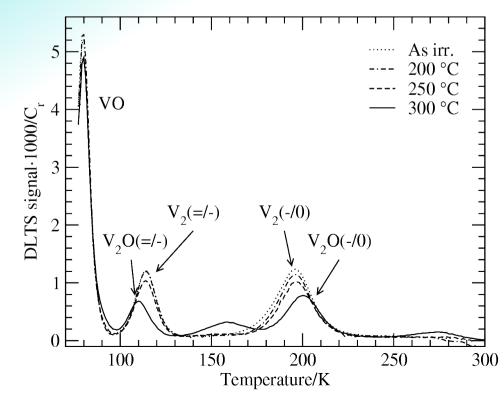


DLTS measurements on sample-set 2 (4 h in deuterium plasma)

$$V_2 + O \rightarrow V_2O$$

VO peak stable

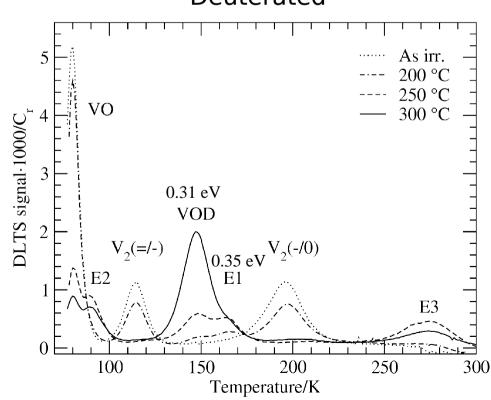
Nondeuterated



 V_2 anneals while VOD and E1 grow Is E1 = V_2D_2 ?

VO peak anneals

Deuterated



Summary



- $V_2 \rightarrow V_2O$ in nondeuterated samples
- Deuterium-assisted annealing of V₂ and VO in deuterated samples
- No peak that can be associated with V_2D_2 is observed shallower than $E_2 0.2 \text{ eV}$
- A peak E1 with energy level $E_c 0.35$ eV is observed $(V_2D_2?)$
- Higher deuterium concentration causes more VO annealing, higher maximum amplitude of the VOD peak and two additional peaks E2 and E3

Future activities



- Isothermal annealing series
- More accurate fitting of the DLTS spectra
- Modelling of the defect dynamics
- Analysis of the spectra after annealing at T > 300 °C